

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Patent No 7,157,385 B2
Patent Issue Date January 2, 2007
Application Serial No. 10/655,699
Filing Date September 5, 2003
Assignee Micron Technology, Inc.
Inventorship Garo J. Derderian et al.
Attorney's Docket No. MI22-2307
Title: Method of Depositing a Silicon Dioxide-Comprising Layer in the Fabrication of Integrated Circuitry

**REQUEST FOR CERTIFICATE OF CORRECTION OF PATENT FOR
APPLICANT MISTAKES and PTO MISTAKES (37 C.F.R. §§ 1.322(a) and 1.323)**

To: Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450
ATTN: Decision and Certificate of Correction
Branch of the Patent Issue Division

From: Mark S. Matkin (Tel. 509-624-4276; Fax 509-838-3424)
Wells St. John P.S.
601 W. First Avenue, Suite 1300
Spokane, WA 99201-3828

Sir:

It is hereby requested that a Certificate of Correction be issued with respect to Patent No. 7,157,385 B2, granted January 2, 2007, in accordance with the Certificate of Correction form attached hereto.

It is noted that errors appear in this patent of a typographical nature of character, as more fully described below. The errors occurred in good faith. Correction thereof does not involve such changes in the patent as would constitute new matter or would require re-examination.

The other error listed on the Certificate of Correction form were apparently incurred through the fault of the PTO as will be disclosed by the records of files in the Office.

Attached hereto, is Form PTO-1050, being suitable for printing.

The exact page and line number where the errors occur in the application file are:

Page 12, paragraph 24;

Page 17, paragraph 32;

Page 18, paragraph 34.

The Director is hereby authorized to charge the \$100.00 fee as required under 37 CFR 1.20(a), or credit any overpayment, to Deposit Account No. 23-0925.

Respectfully submitted,

Dated: 7-12-07

By: 

Mark S. Matkin
Reg. No. 32,268

UNITED STATES PATENT AND TRADEMARK OFFICE
CERTIFICATE OF CORRECTION

PATENT NO. : 7,157,385 B2
DATED : January 2, 2007
INVENTOR(S) : Derderian et al.

It is certified that errors appear in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

Title page 2, OTHER PUBLICATIONS, First Column, please delete "*Agglomeration*" after "Nishiyama et al." and insert --*Agglomeration*--.

Col. 4, line 66, please delete "effect is" after "effect is".

Col. 6, line 67, please delete "'X.'" after "where" and insert --"X"--.

Col. 7, line 31, please delete "an" after "wet".

Page
1 of 1

Mailing Address of Sender:

Mark S. Matkin
Wells St. John P.S.
601 West First Avenue, Suite 1300
Spokane, WA 99201-3828

Patent No. 7,157,385 B2